

CHEMICALLY AMPLIFIED RESIST COMPOSITION AND METHOD FOR
FORMING PATTERNED FILM USING SAME

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ABSTRACT OF THE DISCLOSURE

10 A chemically amplified resist composition which
comprises a base resin reacting in the presence of an
acid, a photo acid generator generating an acid upon
exposure, and a compound having the combination of an
acetal moiety and a site which is eliminated by an acid
15 in its molecule, or which comprises a base resin, which
is a copolymer having the combination of an acetal moiety
and a site eliminated by an acid in one repeating unit
and reacts in the presence of an acid, and a photo acid
generator generating an acid upon exposure.